## Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

## Listing of Claims:

- 1. (canceled)
- 2. (canceled)
- 3. (canceled)
- 4. (canceled)
- 5. (canceled)
- 6. (canceled)
- 7. (canceled)
- 8. (canceled)
- 9. (canceled)
- 10. (canceled)
- 11. (currently amended) A semiconductor integrated circuit device comprising: trenches formed in a semiconductor substrate and defining active regions and dummy regions; and

element isolation insulating films buried in said trenches <u>by polishing an</u>

<u>insulating layer formed over said trenches and said semiconductor substrate</u> such
that said element isolation insulating films serve as element isolation regions,
wherein said dummy regions are formed at a scribing area.

- 12. (previously presented) A semiconductor integrated circuit device according to claim 11, wherein a length of said dummy region is shorter than a distance between external terminals.
- 13. (currently amended) A semiconductor integrated circuit device comprising:

  trenches formed in a semiconductor substrate and defining active regions and dummy regions; and

insulating films buried in said trenches <u>by polishing an insulating layer formed</u>

<u>over said trenches and said semiconductor substrate</u> such that said insulating films

serve as element isolation insulating films;

wherein said dummy regions are formed at a scribing area.

- 14. (previously presented) A semiconductor integrated circuit device according to claim 13, wherein a length of said dummy region is shorter than a distance between bonding pads.
- 15. (currently amended) A semiconductor integrated circuit device comprising: trenches formed in a semiconductor substrate and defining active regions and dummy regions; and

element isolation insulating films buried in said trenches <u>by polishing an</u>

<u>insulating layer formed over said trenches and said semiconductor substrate</u>,

wherein said dummy regions are formed at a scribing area.

16. (previously presented) A semiconductor integrated circuit device according to claim 15, wherein a length of said dummy region is shorter than a distance between external terminals.